

巨玻固能(苏州)薄膜材料有限公司 Jubo Guneng(SuZhou)Thin Film Materials Co., Ltd.

Material材料名称:	SiO ₂ 二氧化硅	
Article No.产品编码:	BoSE-18-00	079.18.00
Delivery Form产品规格:	1.5-3.0mm	筛下颗粒<5%
Material Properties:	Chemical Formula分子式:	SiO ₂
材料特征:	Purity纯度:	>4N
	Typical Impurities杂质类型 [ppm]:	Ca<90 Fe,Si,Ce<30, Pr,La,Nd,Y,Gd<10
	Density-theoretical 理论密度:	2.3 g/cm ³
	Melting Point熔点:	1730 °C
Test Parameters:	Coating Equipment镀膜设备:	ZSS 700
测试参数:	Evaporation Source蒸发源:	Electron Beam Gun电子枪
	Substrate Temp.基底温度:	250 °C
	Process Gas充气压力:	0.5~1x 10 ⁻² Pa Oxygen
	Evaporation Rate蒸发速率:	0.3-0.5 nm/s
Thin Film Properties:	Chemical Composition化学成分:	SiO ₂
薄膜参数:	Refractive Index折射率:	1.46 (520nm <λ< 580 nm)
Remark	Transparency Range透明区域:	200nm~9μm
备注:	Melting Behaviors蒸发习性:	Film densification, good at chemical stability. 成膜致密, 化学稳定性好。

Material Certification声明:

We certify, the material is in compliance with the specifications stated above.

我们证明, 该材料符合上述规范。

Date 日期: 2021-1-19
Certificate No.证书编号: JBSE-Specification 079.18.00